

ABSTRACT

A chemically amplified radiation sensitive composition is provided which comprises a film forming hydroxystyrene based
5 resin in combination with an onium salt precursor which generates a fluorinated alkanesulfonic acid as a photoacid generator. This composition can realize neither corrosion of apparatuses by outgas, nor T-shaped pattern profiles, nor change in linewidth attributable to process time delay, on the other side, high
10 sensitivity and resolution, and good pattern profiles and stability thereof.